

Substitute Form PTO-1449 (Modified) Information Disclosure Statement by Applicant (Use several sheets if necessary) (37 CFR §1.98(b))	U.S. Department of Commerce Patent and Trademark Office	Attorney Docket No. 20228-0013US1	Application No. 10/580,698
	Applicant Damian Fiolka et al.		
	Filing Date November 29, 2006	Group Art Unit 2872	

U.S. Patent Documents							
Examiner Initial	Desig. ID	Document Number	Publication Date	Patentee	Class	Subclass	Filing Date If Appropriate
/J.C./	1	6483573	11/19/2002	Schuster			
/J.C./	2	2009/0115989	5/7/2009	Tanaka			
/J.C./	3	2009/0128796	5/21/2009	Tanaka			
/J.C./	4	2010/0141921	6/10/2010	Omura			
/J.C./	5	2010/0141926	6/10/2010	Omura			
/J.C./	6	2010/0142051	6/10/2010	Omura			

Foreign Patent Documents or Published Foreign Patent Applications								
Examiner Initial	Desig. ID	Document Number	Publication Date	Country or Patent Office	Class	Subclass	Translation	
							Yes	No
/J.C./	7	KR 2000-0076783	12/26/2000	KR			See 1	
/J.C./	8	JP 7-142338	6/2/1995	JPO			Abstract only	
	9	JP 2001-133360	5/18/2001	JPO			X	
	10	JP 2005-108925	4/21/2005	JPO			Abstract only	

Other Documents (include Author, Title, Date, and Place of Publication)		
Examiner Initial	Desig. ID	Document
/J.C./	11	Himel et al., "Design and fabrication of customized illumination patterns for low ki lithography: a diffractive approach," Optical Microlithography XIV, Christopher J. Progler, Editor, Proceedings of SPIE Vol. 4346 (2001).

Examiner Signature /Jade Chwasz/	Date Considered 02/22/2011
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